

SPUTTERING TARGET MATERIAL






Publication number: WO02077317 (A1)

Publication date: 2002-10-03

Inventor(s): HASEGAWA KOICHI [JP]; ISHII NOBUO [JP]; ASAKI TOMOYOSHI [JP] ÷

Applicant(s): ISHIFUKU METAL IND [JP]; HASEGAWA KOICHI [JP]; ISHII NOBUO [JP]; ASAKI TOMOYOSHI [JP] ÷

Also published as:

 EP1371749 (A1)
 EP1371749 (B1)
 US2004055882 (A1)
 US7465424 (B2)
 TW575674 (B)






more >>

Classification:

- international: *C22C5/06; C22C5/08; C23C14/14; C23C14/34; G11B7/258; G11B7/26; C22C5/06; C23C14/14; C23C14/34; G11B7/24; G11B7/26;* (IPC1-7): C22C5/06; C23C14/14; C23C14/34; G09F9/30; G11B7/26; H05B33/10; H05B33/14; H05B33/24

- European: C22C5/06; C22C5/08; C23C14/14; C23C14/34B2; G11B7/258D; G11B7/26

Cited documents:

 JP2001357559 (A)
 JP11025515 (A)
 JP10177742 (A)
 JP2000109943 (A)
 JP9111380 (A)

Application number: WO2002JP02466 20020315

Priority number(s): JP20010076132 20010316

Abstract of WO 02077317 (A1)

A sputtering target material which comprises an Ag alloy comprising Ag, a specific small amount of a metal component (A) selected from among In, Sn and Zn and a specific small amount of a metal component (B) selected from among Au, Pd and Pt and optionally a small amount of Cu. The sputtering target material has a high reflectance and also exhibits excellent resistance to sulfurization.

.....
 Data supplied from the **espacenet** database — Worldwide